

ABSTRACT OF THE DISCLOSURE

SCANNING EXPOSURE METHOD AND
SCANNING TYPE EXPOSURE APPARATUS

In the scanning exposure method of the present invention, a mask and a substrate are moved in a synchronous manner, and first patterns and a second pattern are connectedly exposed on the substrate. At least a portion of the first patterns and at least a portion of the second pattern form a common pattern, and the common pattern and non-common patterns, which differ from the common pattern, are formed in mask as the first patterns and the second pattern. The first patterns and the second pattern are connected by means of the common pattern.

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